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Attorney Docket No. 60188-446
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

RECEIVED
JUN 27 2003
TC 1700

In re Application of
Masayuki ENDO, et al.

Serial No.: 10/032,542

Group Art Unit: 1756

Filed: January 02, 2002

Examiner: Daborah Chacko Davis

For: PATTERN FORMATION METHOD

AMENDMENT UNDER 37 C.F.R. § 1.111

Mail Stop Non-Fee Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the final Office Action mailed March 26, 2003, having a shortened statutory period for response set to expire on June 26, 2003, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend claim 1 as follows:

1. (Amended) A pattern formation method comprising the steps of:

forming a resist film of a chemically amplified resist material including a base polymer having a lactone group and having neither a hydroxyl group nor a carboxylic

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